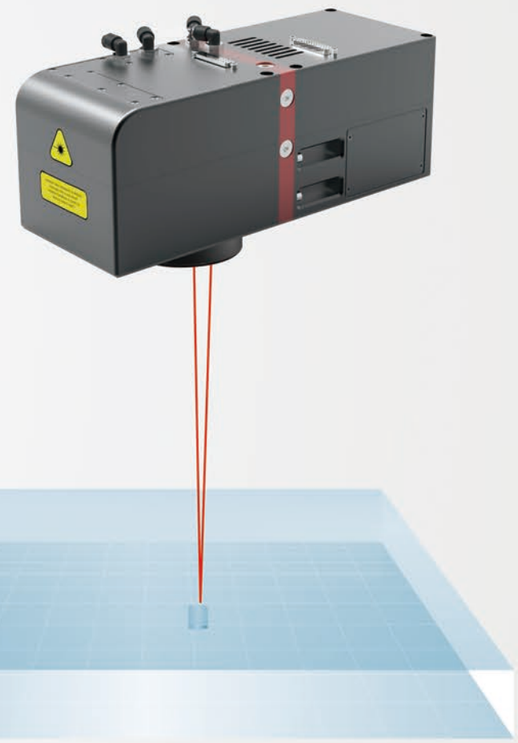
2.5D FE Serial

Support wavelength:355/532/1064nm

Deep engraving, small field micro processing Priority choice for micro-processing

- CNC shell,dust prevention,compact structure,easy to integrate.
- Optional water cooling design, it can be applied to high-temperature drift requirements.
- Adopts the digital pulse width modulation driving technology, owns higher response speed and lower temperature drift.



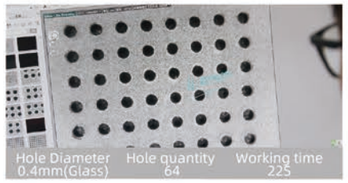
FE10

FE15

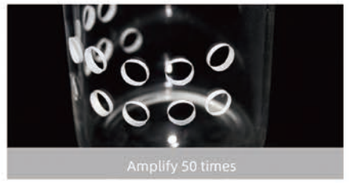
FE20

Highlight: drilling, high precision marking

The focal point is controlled by the optical and is controllable by software, effectively reducing the collapse edge.
Dynamic focus can realize the 3D surface application.
No need for mechanical optical lifting, a simple structure, and easy to achieve automation, improve efficiency.



High efficiency
The dynamic axis and the XY axis are fully software coordinated, and the layered focus compensation is completed in microseconds with high efficiency.



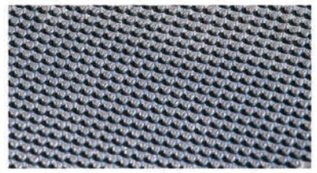
High precision
With the switch of the processing depth, the dynamic axis coordinately adjusts the focal length and adjusts the center spot in real-time, which can achieve higher accuracy than traditional scanhead.

Application Highlight

APPLICATIONS

- Drilling
- Engraving
- Super precision marking

Glass drilling (different shape)



Hard material deep carving

Precision marking

Engraving (knife tool)

2.5D FE Serial

Support wavelength:355/532/1064nm

Product Technical Information

	Technical Info.	Specifications
Items	Output Voltage(VDC)	±15
	Current(A)	10
	Protocol	XY2-100 Protocol
Cooling Condition	Cooling Media	Distilled or de-ionized water plus corrosion inhibitor
	Temperature(℃)	22-28
	Recommended cooling pressure(bar)	2-3
	Recommended flow rate(l/min)	4-6

Product line	Product line	E10			E15			E20	
	Weight（KG）	5.6			6.7			9	
	Size(mm)	297x125x120			339x125x120			337x134x153.5	
Galvanometer Specifications	Version	Standard	Pro	P2	Standard	Pro	P2	Pro	P2
	Tracking error (ms)	≤0.18	≤0.18	≤0.16	≤0.21	≤0.21	≤0.2	≤0.28	≤0.27
	Repeatability(μrad)	8	8	5	8	8	5	8	5
	Temperature drift(μrad/k)	100	100	50	100	100	50	100	50
	Long-term drift (>24h,room temperature)(mrad)	≤0.2	≤0.2	≤0.1	≤0.2	≤0.2	≤0.1	≤0.2	≤0.1
	Max.processing speed (characters/s)(high-quality mode)	600@100x100			650@100x100			500@100x100	
	Operating temperature(℃)	25℃±10℃							

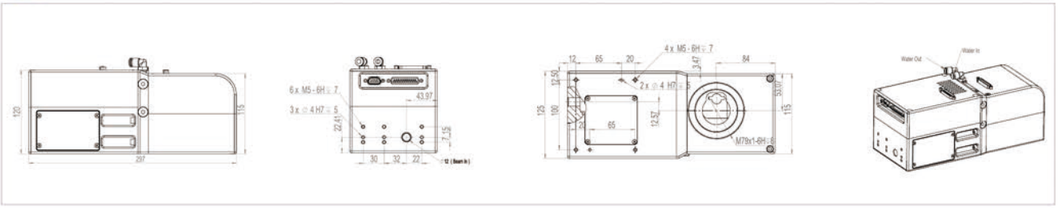
E10 Optical Specifications	Wavelength	**355nm**	**532nm**	**1064nm**
	Aperture Size(mm)	≤10mm	≤10mm	≤10mm
	Input magnification options	2X 2.66X	2X 2.66X	1.16X
	Z depth [1)]		±5mm / ±25mm	

E15 Optical Specifications	Wavelength	**355nm**	**532nm**	**1064nm**
	Aperture Size(mm)	≤15mm	≤15mm	≤15mm
	Input magnification options	2X 2.66X	2X 2.66X	1.66X
	Z depth [2)]		±5mm / ±25mm	

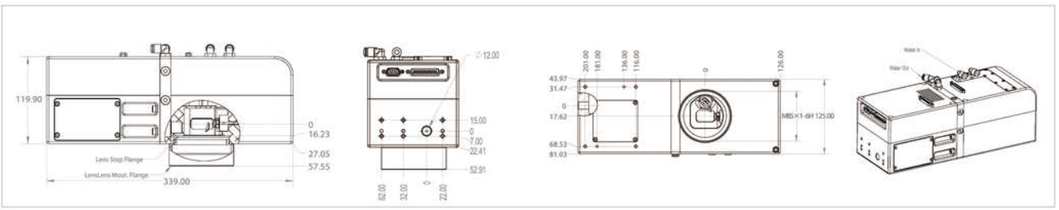
E20 Optical Specifications	Wavelength	**1064nm**
	Aperture Size(mm)	≤20mm
	Input magnification options	2.1X 2.57X 2.66X
	Z depth [3)]	±5mm

1），2），3）Long focal length and short focal length version for option.The manual data is based on F-θ 254 under 150*150mm.

FE10



FE15



FE20